

# IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In Re the Application of

LOF et al.

Ì

Group Art Unit: 1756

Application No.: 10/705,783

Examiner:

Filed: November 12, 2003

Confirmation No.: 5222

For:

LITHOGRAPHIC APPARATUS AND DEVICE MANUFACTURING METHOD

# INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents P. O. Box 1450 Alexandria, VA 22313-1450

Sir:

Pursuant to 37 C.F.R. 1.56, the attention of the Patent and Trademark Office is hereby directed to the following U.S. patent application(s):

Examiner's	First Inventor	Application No.	Filing Date	Enclosed
Initials	No. of the second se			⊠ Specification
27	DIERICHS (081468-0308270)	10/775,326	02/11/2001	<ul><li>☑ Drawings</li><li>☑ Other: stamped receipt card</li></ul>
0.70	DUINEVELD et al. (081468-0308101)	10/773,461	02/09/2004	<ul><li>☒ Specification</li><li>☒ Drawings</li><li>☒ Other: stamped receipt card</li></ul>
	FLAGELLO et al. (081468-0302644)	10/698,012	10/31/2003	<ul><li>☒ Specification</li><li>☒ Drawings</li><li>☒ Other: stamped receipt card</li></ul>
DR	SUWA et al. (Reissue Application of U.S. Patent No. 6,191,429 B1)	10/367,910	02/19/2003	⊠ Specification     □ Drawings     □ Other: stamped receipt card     the cited application relative to

<sup>\*</sup>The Examiner's initials adjacent a citation indicates he/she has considered the cited application relative to the subject application.

It is respectfully requested that these applications and the art cited therein during examination be expressly considered during the prosecution of this application and be made of record in this application. The identification of the above U.S. patent applications is not to be construed as a waiver of secrecy as to those applications now or upon issuance of the present application as a patent.

PLEASE DO NOT PRINT the above information on the patent which results from this application.

الرية	<u>د</u>			TP	~		Υ	No.	# . & & &		Clost	386	- ; ;;	
FORM PTO-	1449 (	modified)		)''	c 💆		Atty.	M#			Cllent	Kei.		3.
		ent of Commerce	- /		mas E.		Dkt. No.		122				Time (E	973
(PW FORM I	PAT-14	449) idemark Office	7	NH 55	2004 5							- T.		377
Palenta	110 116	demark Cinco	13										- TWO	
,			16	BTRAD	EMARIA			306524			P-038	31.02	<u> 20-US</u>	
		DISCLOSURE	STATE				Applicant	t: LOF et	al.					
BY APPLI	ÇAN	T					Appln. N	o.: 10/70	5,783					
),							Filing Da	te: Noven	ber 12, 2	003				
Date: June	22 2(	nna Page	1	of [	1		Examine				oup Art	Unit	1756	
		CUMENTS			1 - 1 - 1 - 1 - 1 - 1 - 1 - 1 - 1 - 1 -		**************************************	-						#4
Examiner's		Document	Date	autorice —cons	Name	175				Class	Sub		Filing	$\Box$
Examiner s Initials*		Number		YYYY		Name	of First In	ventor)			Class	·	Date (if appropr	iate)
DR.	AR	2004/0075895 A1	04/20		LIN						_		-	$\dashv$
DR	BR	2004/0109237 A1	06/2	004	EPPLE et	al.			<del></del>		+		<u> </u>	긕
	CR				<del> </del>						+			$\dashv$
	DR				<del> </del>						+			$\dashv$
	ER			<del>-</del>	<u> </u>		1				+		·	
	FR				<del> </del>						+			-
	GR										+			
	HR								-,		+	-		
<u> </u>	IR				<u> </u>	_								$\overline{}$
	JR		<del></del>		<del></del>						+		<del></del>	
E-FA ( John or box ) Chippens	KR			and karen		<b>49</b> 0.93	<b>第四个人的基础的</b>				nglish		Translati	00
FOREIGN	PATE	NT DOCUMENTS				26 35 S			<b>一种学生的</b>	1.125702.007	bstract		Readily	
	ł	Document	Date MM/YY		untry	Inve	ntor Name	•		ŀ			Available	•
		Number		' '						E	nclosed	No	Enclose	No
70	<del>  </del>	1410 00/077007	00/2002	PC		POS	TALSKI		+				<u> </u>	П
<u>D. R.</u>	LR.	WO 03/077037	09/2003	<del></del>	RMANY	+	TPHAL et	al	<del> </del>			Х		П
DK.	MR	DD 206 607	04/1985		RMANY		RR et al.	<u> </u>				X		$\top$
D.R.	<del>,</del>	DD 221 563	104/1303	- 3-	I VIANON I	1	TOT CT CIT.		<del>                                     </del>		· .		<u> </u>	
	OR		-			+			<del></del>					$\vdash$
	PR		<u> </u>	$\dashv$		+			_		<del> </del>			Π
	QR			_		<del>                                     </del>								
	RR					<del>                                     </del>						Г		I
<u> </u>	TR	<u></u>	<del> </del>			<del>                                     </del>								Ī.
OTHERWS		i 19 In this order Aut	hor Tille	Je de	dical Nam	e pa	e Perine	nt Pages	retch			Ī		
	UR	B. LIN, "The k3 coe	ய <u>ுள்ளார்.</u> fficient in	nonnar Macilic	axial J/NA	scaling	equations	for resolut	ion, depth	of.				T
D.K	lok.	focus, and immersi	on lithogr	aphy, J	. Microlith.,	Micro	fab., Micros	syst 1(1):7	-12 (2002)			<u> </u>		ــــ
	VR	,										_		<u> </u>
	WR											<u> </u>	ļ	↓_
	XR											ـــ		<del> </del>
	YR			_								<u> </u>		╀
	ZR											<del> </del>	<del>  -</del>	╀
	AAR													+
	BBR								. <u> </u>			╀╌		+
	CÇE	<u></u>			<del>- :</del>			·		-1		<u> </u>	<u> </u>	<u> </u>
Examiner	B	intland						nsidered:						.,
*EXAMINE	R:	Initial if citation cons	idered, w	hether	or not citati	on is i	n conforma	nce with M	PEP § 609	). Drav	line the	ough	citation	if.
not in confo	<u>manc</u>	e and not considere	<u>d. Include</u>	сору с	TINIS TORM	with h	ext commu	nication to	Applicant.					

FOR	M PTO-	1449	(modified)						Atty.	M#				Client	Ref.		
	-		ent of Commerce	)					Dkt. No.	İ							
	FORM I		(449) ademark Office						1	l							
'	-alent a	110 11	ademark Office										į				
										306	5524		F	·-03	81.0	20-US	
INF	ORMA	TIOI	N DISCLOSUE	RE ST	ATEN	MENT			Applicant:		Joeri LOF 6	t al.					
	APPLI								•								
									Appln. No	.: 1	FO BE ASS	HGNE	D- /	0/	70	578	<u>,</u>
									Filing Date	e: I	November	12, 20					<u> </u>
Date	: No	vem	ber 12, 2003	Page	1	of	3	7	Examiner					it U	nit <del>. L</del>	Inknow	
U.S.			OCUMENTS		· ·	<del></del>			<del></del>		·						<del>-</del>
	niner's		Document		Date		Name					Clas	ss S	Sub	•	Filing	-
Initia		1	Number			<b>YYY</b>		lame	of First Inv	entor	)	""		Class	s	Date	
_							<u> </u>				<u> </u>					(if approp	riate)
1	<u>.R</u> .	AR	3,573,975		04/19		Dhaka et	al				117		12			
1		BR	3,648,587	<del></del>	03/19		Stevens				<u>,</u>	95 430		4		<b></b>	
		CR	4,346,164		08/19		Tabarelli e	et al.				111					
		DR	4,396,705		08/19		Akeyama	et al.	<del></del>			430		26		<u> </u>	
		ER	4,480,910		11/19		Takanash	i et al.			•	355	-	0		<u> </u>	•
		FR	4,509,852		04/19		Tabarelli e	et al.				355	<del></del>	0		<u> </u>	
		GR	5,040,020		08/19		Rauschen	bach e	et al.			355		64 64			
HR 5,121,256 06/1992 Corle et al.									359								
IR 5,610,683 03/1997 Takahashi												355	5			ļ	
		JR	5,715,039		02/19		Fukuda et	al.	<del></del>	•	•	355		3		<del>                                     </del>	
		KR	5,825,043		10/19		Suwa		-			250		48		<b>├</b> ──	
<u> </u>		LR	5,900,354		05/19		Batchelde	r				430	-	95_		<del> </del>	
	ν <u> </u>	MR	6,191,429		02/20		Suwa					250	-	48		<b>├</b> ──	
1	<u>K</u>		6,560,032		05/20	03	Hatano					359	<del>T</del>	56		<u> </u>	
FOR	EIGN F	ATE	NT DOCUMEN	TS		<del></del>		·					Engli: Abstr			Translati Readily	ion
			Document	Date		Count	try	Inver	itor Name					400		Available	е
			Number	MM/Y	* * *											<u> </u>	_
┝	<u> </u>							<u> </u>					Enclo	sed	No	Enclose	No
	R.	OR	WO 99/49504	09/199		PCT		-	ni et al.		<del>-</del>		X		<del> </del>	X	┼
		_	EP 0023231	02/198		Europ		<del>                                     </del>	elli et al.				X		<u> </u>		┼
		QR RR	EP 0418427 EP 1039511	03/199		Europ		Miyak					X X			X	┼
-		SR	DD 224448	07/198		Germa		<del>                                     </del>	kimi <i>et al.</i> e et al.				<del>                                     </del>	$\dashv$	X	X	╆
		TR	DD 242880	02/198		Germa		Kuch					$\vdash$	$\dashv$	^ X		$\vdash$
			FR 2474708	07/198		France		Letell	ier				<u> </u>	$\dashv$	x		$\vdash$
		VR	JP 62-065326	03/198		Japan		Moriu					×	$\dashv$			$\vdash$
$\overline{}$		_	JP 62-121417	06/198	-	Japan	_	Naka					X	$\dashv$			$\vdash$
7	$\mathcal{R}$	XR	JP 63-157419	06/198		Japan		Naka					x				
ОТН	ER (Inc		g in this order A	uthor.	Title	<del></del>				Page	es etc.)		f	_			Ħ
			EP Search Repo								50, 6.5.7		1				
<b>D</b> .	2		M. Switkes et al. December 17, 2	, "Imme						Lab,	Orlando 200	1-1,					П
0	R	AAR	M. Switkes et al. 6, November/De	, "Imme				nm",	J. Vac. Sci.	Techr	nol. B., Vol.	19, No.					
2	R.	BBR	M. Switkes et al. September 4, 20	, "Imme			_	s for th	e 50 nm No	de*, 1	57 Anvers-	١,		$\neg$			П
Exam	iner 🔏	<del>Q</del>	nto of						Date Cons	idere	d: 5//	. /-	200	<u> </u>	<u>_</u>		$\dashv$
_	MINER		nitial if citation co	nsidere	d, whe	ther or	not citation					9. Dra	w line	thm:	uah (	citation i	=
		nance	and not conside	red. Inc	lude c	opy of t	his form wi	ith nex	t communic	ation	to Applicant	<b></b>			-9"		

2851

To: U.S. De	RM PTO-1449 (modified) U.S. Department of Commerce V FORM PAT-1449) Patent and Trademark Office								M#			Clie	nt Ref	•		
									306	5781		P-0	381.0	010-US		
INFORMA BY APPL		DISCLOSURE	E STA	TEME	NT			Applicant		Joeri LOF	et al.	•				
								Appin. No	).: ~	TO BE AS	SIGNE	Đ /0 /	171	578	23	
							_	Filing Dat	e: N	ovember 1	2, 200					
Date: Nov	ember	12, 2003	Page	2	of	3	<u>l                                     </u>	Examiner	: Unl	known	Gre	oup Art l	Jnit:	Unknow	n - 2	285/
U.S. PATE	NT DC	CUMENTS	•	<del>,</del>						<u>-</u>						•
Examiner's Initials*		Document Number		Date MM/Y	<b>/</b>	Name (Family	Name	of First In	vent	or)	Clas	ss Sub Cla		Filing Date	oriete)	
DR.	CCR	6,603,130		08/200	3	Bisscho	ps et a	1.			250	492	.1	(ii appro	Jilate)	
	+	6,633,365		10/200	3	Suenag	<del></del>				355	53		1		
	EER	2002/0163629		11/200	2	Switkes	et al.				355	53				
<u>_</u>	FFR	2003/0123040		07/200	3	Almogy					355	69				
DX_	GGR	2003/0174408		09/200	3	Rostalsi	ci et al.			_	359	642		<u> </u>		
	HHR					ļ				_				<u> </u>		
	IIR				-					<del></del>				ļ		
	JJR							<del></del>			-			<u> </u>		*
	KKR											-			.	
	LLR MMR		-			<b>-</b>		<del></del> _		· · · · · · · · · · · · · · · · · · ·	_	<del></del>		-		
	NNR										+			<del>  -</del>		
	OOR	<u> </u>				<b></b>					+	_		+	<del></del>	
	PPR					<del></del>					+	-		+		
FOREIGN I	•	IT DOCUMENTS	3		<del></del>	<del> </del>					<del>-                                    </del>	English	-	Translat	ion	
		Document Number	Date MM/Y	<b>YYY</b>	Cour	ntry	Inven	tor Name				Abstract	·	Readily Available	e	
D.R.	000	JP 04-305915	40/400	<u> </u>	1		0	-4 -4				Enclosed	No	Endose	No:	
~ ~		JP 04-305915 JP 04-305917	10/199		Japai		Ozeki					X	+	<b></b>	H	
		JP 06-124873	05/199		Japai		Ozeki					x	+	×	H	
		JP 07-220990	08/199		Japai		<del> </del>	la et al.	-			×	+	<del>                                     </del>	H	
		JP 10-228661	08/199		Japar		Kurok		-			x	+	<del>                                     </del>	H	
		JP 10-255319	09/199		Japar	-	<del> </del>	iga et al.				x	$\vdash$	†	H	
		JP 10-303114	11/199		Japar	-	Suwa					х	$\top$	x		
V	XXR	JP 10-340846	12/199	8	Japar		Kudo					х	$\vdash$	x	$\Box$	
D.R.	YYR	JP 2001-091849	04/200	11	Japar	n	Aizaki	et al.				X			$\Box$	
	ZZR															
OTHER (Inc	gnibuk	in this order Au	thor, T	itle, Pe	riodic	al Name	, Date	, Pertinent	Pag	es, etc.)						
D.2		B.J. Lin, "Drivers, September 2002	<u> </u>				_				<u> </u>					
DR		B.J. Lin, "Proximit No. 11B, April 197			ugh L	iquid", IB										
Examiner		thede-								d: 5/6						
*EXAMINER	R: In	itial if citation cons and not considere	sidered,	whethe	r or n	ot citation	n is in c	conformance	e with	MPEP § 6	09. Dra	w line the	ough	citation i	if	
TOTAL COMON	11011100	end not mismete	v. mull	ne cob)	UI UII	na ioniu M	ui nex	<u> </u>	auon	w Applican	ι				- 1	

FORM PTO-						-		Atty.	M#		- 1	Client	Ref.		
		ent of Commerce						Dkt. No.							
(PW FORM)		1449) ademark Office						1							
		- Coman Omoc							:		- 1				
									3067.81			P-03	81.0	10-US	
		N DISCLOSUF	RE ST	ATEN	MENT			Applicant:	Joeri LOF e	t al.					_
BY APPLI	CAN	l E						A = -1= A1=	TO DE 400	1015		. /			
								Appin. No				2/7	70	5783	2.4
Data: Nav	h-	vr 12 2002	Page	3	of	3	٦		e: November 12			<u> </u>	- '		
Date: Nov			raye	3	loi	1 3		<u> Examiner:</u>	Unknown	JGro	oup A	עני טו	nit: \	Inknow	<u> </u>
Examiner's	1	OCUMENTS Document		Date		Name			· · · · · · · · · · · · · · · · · · ·	Iciaa	. 1	<u> </u>		cu:	
Initials*		Number			<b>/</b>		Jama	of First Inv	ontor)	Clas		Sub Class	2	Filing Date	
IIIIIais	<u> </u>	Number		IAIIAI	·	(Failily i	Valifie	OI FIISUMV	entor)	_	l`			(if approp	nate
	ccc	;													
	DDD	)													
	EEE					<u> </u>									
FOREIGN F	PATE	NT DOCUMEN	TS						••		Engi			Translat	ion
-		Document	Date		Coun	try	Inver	ntor Name			Abst	ract		Readily Available	_
		Number	MM/Y	YYY											
	<u> </u>						<u> </u>				Encl	osed	20	Endose	No
٠.	FFFI										<u> </u>				
	GGC		<u> </u>		<u></u>						<u> </u>				<u></u>
OTHER (Inc		g in this order A									]				
D.R.	ннн	B.J. Lin, "The Pa	ths To	Subha	If-Micro	meter Opti	ical Lit	hography", S	SPIE Vol. 922,			٠.			İ
1	IIIR	Optical/Laser Mid G.W.W. Stevens	, "Redu	ction	of Wast	e Resulting	g from	Mask Defec	ts", Solid State		1				
	1110	Technology, Aug S. Owa et al., "In									-				₩
	3337	Microlithography						iormance a	nd issues", SPIE						
	KKK							Lithography	/", Proc. SPIE 504	0					Г
	LLLF	Nikon Precision I 2003	Europe	Gmbl	l, "Inve	stor Relation	ons – N	likon's Real	Solutions", May 1	5,					<u> </u>
	MMN	H. Kawata et al. Greater than Uni	, "Optic tv". Mic	ai Proj	ection l	_ithography	y using	Lenses wit	h Numerical Aperl	ures					
	NNN		al., "Lic	quid In	nmersio	n Deep-Ul	traviole	et Interferor	etric Lithography'	, J.				-	
	000		, "Imme						URE FAB Internat	ional,					
	PPP		"Fabric	ation o	of 0.2μπ	n Fine Patt	erns U	Ising Optica	Projection Lithog	raphy			-		
DZ.	QQC		1/8µm (	Optical	Lithog	raphy", J. V			B., Vol. 10, No. 6,			1			
<u> </u>	RRR		noci ic	, p	. 000 <u>2</u>	0000					<u> </u>	一十			$\vdash$
	SSSI			-									$\dashv$		
	TTF										t —		_		
	UUU														
	<b>~</b>				_										
	ww														
	XXX														
	YYY											$\Box$			
Examiner	ALK	utt edg						Date Cons	idered: 5/6	120	20:	1			
EXAMINER	t: Ti	nitial if citation cor	nsidere	d, whe	ther or	not citation	is in c	onformance	with MPEP § 609				ugh c	itation if	f
not in conform	nance	and not consider	red. Inc	lude c	opy of t	<u>his form wi</u>	th next	communica	ation to Applicant.				_		

	<b>.</b>											——			
FORM PTO-								Atty.	₩#			Clie	ent Ref.		
		ent of Commerce						Dkt. No.							
(PW FORM F															
Patent a	nd Ira	ademark Office												•	
	•							081468	0306	524		P-(	0381.0	20-US	
					· 				<u> </u>	14.05.4.4			·		
INFORMA BY APPLI		I DISCLOS <b>VA</b> E T	ह्य	ATEN }	IENT			Applicant	: Joe	ri LOF et al.					
		· /	7	台				Appln. No	o.: 10	/705.783					
			2004	(بير				<del></del>		vember 12,	2003				
D-4 14	. 24	2004 B		₽ <del>/</del>	of	[4	٦				$\overline{}$		Linited		
Date: March				ו ע	101	[ ]	<u> </u>	Examiner			Gro	JD Art	Onit. 4	<del>Inassig</del>	Bed_
	IT DO	DOUMENT STADEN				, ' '	<u> </u>				1			1	
Examiner's		Document		Date		Name					Class			Filing	
Initials*		Number		MM/\	$\Upsilon \Upsilon \Upsilon$	(Family N	lame	of First Inv	entor/	) .		Cla	ass	Date	
						<del></del>					<del> </del>	<del></del>		(if approp	oriate)
	AR_	<del></del>												<del>                                     </del>	
	BR			<u> </u>				•			ļ			┞—	
	CR							·-			ļ.,,				
	DR			<u> </u>								<u> </u>		<u> </u>	
	ER			,											
	FR														
	GR	···													
	HR				,		-				·	$\neg$		<u> </u>	
1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1		NT DOCUMENTS	<b>5</b>		viji trakt		in this		A, I	a de la companya de l		English		Translat	tion
FUREIGN	AHE	1 <del></del>	T		T	<u> </u>	<u> </u>	vessy on tops	1,20,140 y 1	HW 7-74 2	<u> </u>	Abstrac		Readily	
		Document	Date	; YYYY	Coun	try	Inver	itor Name						Available	е
•		Number		1111							٠,			<del> </del>	<del>_</del> _
70			ļ		<u> </u>	<del></del>	<del> </del>					Enclose	ed No	Endose	No
D.K.	IR_	JP 07-132262	05/1		Japan	1	Hirak	awa et al.				X		<b></b>	4
	JR	JP 58-202448	11/1	983	Japan		Kawa	mura et al.				X		<u>L</u>	
<u> </u>	KR	WO 2004/019128	03/2	004	PCT		Omur	a et al.			·				$\bot$
DR.	LR	WO 03/077036	0920	03	PCT		Schu	ster				X			
	MR		ļ								,			<u>                                     </u>	
	NR													ļ	
	OR		-												
	PR									· · · -					$\Box$
	QR													†	$\sqcap$
	RR					-					i		$\top$	<del></del>	${}^{+}$
342- 4		g in this order Au	is soir	TIME		Maria		- D. A. 1782	المراجعة				+		+
		ſ													
ロカア	SR	Copy of Europea January 20, 2004		arcn F	кероп	TOT EP AP	piicati	ON NO. UZA	23182	2.3 dated			ŀ		
1	TR	S. Owa et al., "Upd		n 102r	m imm	occion ove		tool" Litho	Eonis	. Internation	,		+-	<del> </del>	+
	IK	SEMATECH, Los							roiuii	i, internation	<b>"</b>				
	UR	H. Hata, "The Deve							Forum	. Internationa	,		1		$\dagger \Box$
		SEMATECH, Los													
		T. Matsuyama et a 65, March, 2004	I., "Ni	kon Pr	ojectio	n Lens Upo	date", S	SPIE Microl	ithogra	aphy 2004, 5	377-				
		*Depth-of-Focus E	nhan	emen	Llsing	High Refra	active I	ndex Laver	on the	e Imaging La	ver"		$\top$	<del></del>	$\dagger \dashv$
		IBM Technical Disc									, ,				Ш
DR.		A. Suzuki, "Lithogr 2004	aphy	Advan	ces on	Multiple Fr	onts",	EEdesign,	EE Tir	nes, January	5,				
	ΥŖ	1											1		$\dagger$
Examiner	( )	The						Date Con	sidere	ed: 5/6/	120		<del></del>		<del></del>
*EXAMINER	)	nitial if aitation acco	ido	d 1.5-	ther	not sitetic							hrough	oitotio=	<del></del>
		nitial if citation cons									. Drav	v mie u	irougn	GLEUON	"

Docket Number: 081468-0306524 Client Reference: P-0381.020-US

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Re the Application of ERI LOF et al.

**Group Art Unit:** 

pplication No.: 10/705,783

**Examiner: Unassigned** 

Filed: November 12, 2003

Confirmation No.: Unassigned

For: LITHOGRAPHIC APPARATUS AND DEVICE MANUFACTURING METHOD

### **INFORMATION DISCLOSURE STATEMENT**

Commissioner for Patents P. O. Box 1450 Alexandria, VA 22313-1450

Sir:

Pursuant to 37 C.F.R. 1.56, the attention of the Patent and Trademark Office is hereby directed to the following U.S. patent application(s):

Examiner's Initials	First Inventor	Application No.	Filing Date	Enclosed
學、研究、和	<b>华兴建筑建设。</b>			THE STATE OF THE S
D.Z.	Joeri LOF et al.	10/705,805	11/12/2003	<ul> <li>☒ Specification</li> <li>☒ Drawings</li> <li>☒ Other: stamped receipt card</li> </ul>
	Helmar VAN SANTEN et al.	10/743,271	12/23/2003	<ul> <li>☑ Specification</li> <li>☑ Drawings</li> <li>☑ Other: stamped receipt card</li> </ul>
	Johannes C.H. MULKENS et al.	10/743,266	12/23/2003	<ul> <li>☒ Specification</li> <li>☒ Drawings</li> <li>☒ Other: stamped receipt card</li> </ul>
	Klaus SIMON et al.	10/724,402	12/01/2003	⊠ Specification     □ Drawings     □ Other: stamped receipt card
	Joannes T. DESMIT et al.	10/705,804	11/12/2003	<ul> <li>✓ Specification</li> <li>✓ Drawings</li> <li>✓ Other: stamped receipt card</li> </ul>
	Antonius T.A.M. DERKSEN et al.	10/705,785	11/12/2003	<ul> <li>✓ Specification</li> <li>✓ Drawings</li> <li>✓ Other: stamped receipt card</li> </ul>
	Arno J. BLEEKER	10/715,116	11/18/2003	<ul> <li>✓ Specification</li> <li>✓ Drawings</li> <li>✓ Other: stamped receipt card</li> </ul>
	Bob STREEFKERK et al.	10/719,683	11/24/2003	Specification     Drawings     Other: stamped receipt card
D.R.	Joeri LOF et al.	10/705,816	11/12/2003	<ul> <li>✓ Specification</li> <li>✓ Drawings</li> <li>✓ Other: stamped receipt card</li> </ul>

The Examiner's initials indicates he/she has considered the cited application relative to the subject application.

D. R.   AR   2004/0000627A1   01/01/2004   Karl-Heinz SCHUSTER   D.   BR   6,660,547   07/29/2003   WATSON et al.   D.   C.   2004/021844 A1   02/05/2004   Yutaka SUENAGA   D.   C.   C.   C.   C.   C.   C.   C.	(PW FORM	epartr PAT-	nent of Commerce	FEB	E 20 201	OFFICE LLIS			Atty. Dkt. No.	M#	:			Client	Ref.	,	
Date: February 20, 2004 Page 1 of 1 Examiner: Unassigned Group Art Unit: Unrescigned Seaminer: Unassigned Group Art Unit: Unrescigned Inventor)  Distribution of the Inventor of First Inventor			(	TATE	TRADEV	KET			081468	03065	24		F	≥-03	81.0	20-US	
Appin. No.: 10/705,783   Filing Date: November 12, 2003   Examiner   Document   Date   Name   MM/YYYY   Family Name of First Inventor)   Class   Sub   Class   Date   Principal   Class   Date   Class   Date   Da				RE ST	ATEN	MENT			Applicant	: Joeri	LOF et al	l <b>.</b>					
Date   Per   Date   D			•						Appln. No	o.: 10/7	05,783						
BYS-PATIENTED GENMENTS  Examiner Number Nar Nar Nar Nar Nar Nar Nar Nar Nar Na						, ·		_	Filing Dat	e: Nov	ember 12	, 2003					
Examiner Number Number New (Family Name of First Inventor)  Are 2004/0000527A1 01/01/2004 (Aarl-Heinz SCHUSTER					1	<del></del>	1	1	Examiner	: Unas	signed	Gro	oup A	vrt Ur	nit: E	Leisaan	ned
Number	U-S-PATE	NTE			<u> </u>		<u> </u>		2 257 A	16 1 1					2. 2. A.	1	·; ·
DR						<b>/</b>	i .	Name	of First Inv	/entor)		Clas			5		
DR   0.00,547   07/29/2003 WATSON et al.	Initials*	<u> </u>			<u> </u>											(if approp	riate)
CR SUDUST UT SUDUSTION OF AUTOMOST UT SUDUSTICATION OF AUTOMOST UT SUDSTICATION OF AUTOMOST UT SUDOST UT SUD	D.R.	AR		\1	+		<u> </u>								<u> </u>		
DR ER ER GR GR GR HR JR	D.K	t	<del></del>		<del>                                     </del>		t		•			<u> </u>	$\perp$				
ER FR GR HR HR JR JR JR KR LR LR Document Number  Enclosed No E	D.K.	<del>                                     </del>	2004/0021844	<u> 41</u>	02/05	<u>5/2004</u>	Yutaka S	UEN/	AGA			<del>  -</del>	<del>-  </del>			ļ	
FR GR HR IR IR JR JR KR LR LR MR FOREIGN PATENT DOCUMENTS  Document Number MM/YYYY Number MM/YYYY  Foreign Patent Document Number MM/YYYY  Number MM/YYYY  Inventor Name  Foreign Patent Document Number MM/YYYY  Foreign Patent Document Number Numbe		+			<del> </del>							-	_		·	<del> </del> -	
GR HR IR JR JR JR KR LR LR MM POREIGN PATENT DOCUMENTS  Document Number  MM/YYYY  Number  Date MM/YYYY  Enclosed No Enclose No Enclosed No Enclose No Enclosed No Enclose No RR OR OR RR OR RR SR SR TR UR UR VR WR OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)  XX H. Hogan, "New Semiconductor Lithography Makes a Splash", PHOTONICS SPECTRA, Photonics TechnologyWorld, October 2003 Edition, pgs. 1-3  XX S. Owa and N. Nagasaka, "Potential Performance and Feasibility of Immersion Lithography", NGL Workshop 2003, July 10, 2003, Slide Nos. 1-33.  ZR AAR BBR CCR Examiner  Date Considered: 5/1/20 455  *EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if	<u> </u>	1		<del></del>	ļ							+	<del></del> -			<del> </del>	
HR IR IR IR JR JR KR LR LR MR FOREIGN PATENT DOCUMENTS  Document Number  Number  Date MM/YYYY  English Abstract  Abstract  Readily Available  Enclosed No Enclose No PR OR PR OR RR SR SR TR UR UR VR WR  OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)  XR H- Hogan, "New Semiconductor Lithography Makes a Splash", PHOTONICS SPECTRA, Photonics TechnologyWorld, October 2003 Edition, pgs. 1-3  XR S. Owa and N. Nagasaka, "Potential Performance and Feasibility of Immersion Lithography", NGL Workshop 2003, July 10, 2003, Slide Nos. 1-33.  ZR AAR BBR CCR Examiner  Date Considered: S// 22 65  EXAMINEER: Intidal if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if		1	·		<del> </del>				<u> </u>				$\dashv$			<del> </del>	
R		<del> </del>										+	$\dashv$			<del>                                     </del>	
JR KR LR LR MR FOREIGN PATENIT DÖCUMENTS  Document Number MM/YYYY Country Inventor Name  NR  OR OR OR OR RR  GR  GR  GR  GR  GR  G		<del></del>						-					$\rightarrow$				
KR LR MR  FOREIGN PATENT DOCUMENTS  Document Number  MM/YYYY  Document Number  MM/YYYY  Inventor Name  English Abstract Readily Available  Enclosed No Enclose No  Enclosed No Enclose No  Readily Available  Available  Translation Readily Available  Readily Available  Invalid if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if		<del> </del>	-									+	$\dashv$	_			
LR MR  FOREIGN PATENT DOCUMENTS  Document Number  MM/YYYY  MM/YYYY  Inventor Name  English Translation Readily Available  Enclosed No Endose No  Enclosed No Endose No  Enclosed No Endose No  RR  OR  RR  OR  RR  SR  SR  TR  UR  UR  UR  VR  WR  OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)  XR H. Hogan, "New Semiconductor Lithography Makes a Splash", PHOTONICS SPECTRA, Photonics TechnologyWorld, October 2003 Edition, pgs. 1-3  XR  ARR  BBR  CCR  Examiner  Date Considered: 5/1/20 55  PEXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if	<del></del>											+	$\dashv$			<del>                                     </del>	
MR  FOREIGN PATENT DOCUMENTS  Document Number  NM/YYYY  Document Number  NR  OR  OR  OR  RR  GR  SR  SR  UR  UR  UR  UR  UR  UR  UR  U				<del>-</del>								<del> </del>	$\dashv$				
Document Number   Date   MM/YYYY   Country   Inventor Name   Abstract   Readily Available		1									-	<del>                                     </del>					
Document Number   Date   MM/YYYY   Country   Inventor Name   Abstract   Readily Available	FOREIGN	PATI	ENT DOCUMEN	TS				<del></del>				<del></del>	Engli	ish		Translati	ion
NR OR OR OR PR QR RR SR SR UN UN UN UN UN UN UN UN UN UN UN UN UN			Document	Date	YYY	Coun	try	Inver	ntor Name				Abst	ract			•
OR PR OR	<b></b>	<u> </u>		ļ		<u> </u>		-		_			Enclo	osed	No	Endose	No
PR QR QR RR SR TR UR VR WR OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)  XR H. Hogan, "New Semiconductor Lithography Makes a Splash", PHOTONICS SPECTRA, Photonics TechnologyWorld, October 2003 Edition, pgs. 1-3  XR S. Owand N. Nagasaka, "Potential Performance and Feasibility of Immersion Lithography", NGL Workshop 2003, July 10, 2003, Slide Nos. 1-33.  ZR AAR BBR CCR Examiner Date Considered: 5/1/ 20 65*  *EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if		+		<del> </del>		<b>}</b>		<del> </del>			_		↓			<b> </b>	$\sqcup$
QR RR RR SR UR UR VR WR OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)  XR H. Hogan, "New Semiconductor Lithography Makes a Splash", PHOTONICS SPECTRA, Photonics TechnologyWorld, October 2003 Edition, pgs. 1-3  XR S. Owa and N. Nagasaka, "Potential Performance and Feasibility of Immersion Lithography", NGL Workshop 2003, July 10, 2003, Slide Nos. 1-33.  ZR AAR BBR CCR Examiner Date Considered: 5/1/20 45  *EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if	<del></del>		<u> </u>	<del> </del>		<del> </del>		<del> </del>					—	$\dashv$			$\vdash$
RR SR TR UR VR WR  OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)  XR H. Hogan, "New Semiconductor Lithography Makes a Splash", PHOTONICS SPECTRA, Photonics TechnologyWorld, October 2003 Edition, pgs. 1-3  XR S. Owa and N. Nagasaka, "Potential Performance and Feasibility of Immersion Lithography", NGL Workshop 2003, July 10, 2003, Slide Nos. 1-33.  ZR AAR BBR CCR  Examiner  Date Considered: 5/1/ 2P 55  *EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if		1		ļ		<del> </del>		<del> </del>					+-	$\dashv$		<u> </u>	$\vdash$
SR  TR  UR  VR  WR  OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)  RR  H. Hogan, "New Semiconductor Lithography Makes a Splash", PHOTONICS SPECTRA, Photonics TechnologyWorld, October 2003 Edition, pgs. 1-3  RR  S. Owa and N. Nagasaka, "Potential Performance and Feasibility of Immersion Lithography", NGL Workshop 2003, July 10, 2003, Slide Nos. 1-33.  ZR  AAR  BBR  CCR  Examiner  Date Considered: 5/1/20 45  *EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if		1		<del>                                     </del>		f			<del></del>				$\vdash$			<del>                                     </del>	Н
TR UR UR VR WR OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)  Representation of the Semiconductor Lithography Makes a Splash", PHOTONICS SPECTRA, Photonics TechnologyWorld, October 2003 Edition, pgs. 1-3  Representation of the Semiconductor Lithography Makes a Splash", PHOTONICS SPECTRA, Photonics TechnologyWorld, October 2003 Edition, pgs. 1-3  Representation of the Semiconductor Lithography Makes a Splash", PHOTONICS SPECTRA, Photonics TechnologyWorld, October 2003 Edition, pgs. 1-3  Representation of the Semiconductor Lithography Makes a Splash", PHOTONICS SPECTRA, Photonics TechnologyWorld, October 2003 Edition, pgs. 1-3  Representation of the Semiconductor Lithography Makes a Splash", PHOTONICS SPECTRA, Photonics TechnologyWorld, October 2003 Edition, pgs. 1-3  Representation of the Semiconductor Lithography Makes a Splash", PHOTONICS SPECTRA, Photonics TechnologyWorld, October 2003 Edition, pgs. 1-3  Representation of the Semiconductor Lithography Makes a Splash", PHOTONICS SPECTRA, Photonics TechnologyWorld, October 2003 Edition, pgs. 1-3  Representation of the Semiconductor Lithography Makes a Splash", PHOTONICS SPECTRA, Photonics TechnologyWorld, October 2003 Edition, pgs. 1-3  Representation of the Semiconductor Lithography Makes a Splash", PHOTONICS SPECTRA, Photonics TechnologyWorld, October 2003 Edition, pgs. 1-3  Representation of the Semiconductor Lithography Makes a Splash", PHOTONICS SPECTRA, Photonics TechnologyWorld, October 2003 Edition, pgs. 1-3  Representation of the Semiconductor Lithography Makes a Splash", PHOTONICS SPECTRA, Photonics Technology Make		1		<del>                                     </del>				<del> </del>					†			<u> </u>	Н
UR VR WR  OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)  XR H. Hogan, "New Semiconductor Lithography Makes a Splash", PHOTONICS SPECTRA, Photonics TechnologyWorld, October 2003 Edition, pgs. 1-3  YR S. Owa and N. Nagasaka, "Potential Performance and Feasibility of Immersion Lithography", NGL Workshop 2003, July 10, 2003, Slide Nos. 1-33.  ZR AAR BBR CCR  Examiner  Date Considered: 5/1/20 55*  "EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if	<u> </u>	1		†				<del>                                     </del>		+			+		-	<del>                                     </del>	╁┤
VR WR OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)  XR H. Hogan, "New Semiconductor Lithography Makes a Splash", PHOTONICS SPECTRA, Photonics TechnologyWorld, October 2003 Edition, pgs. 1-3  YR S. Owa and N. Nagasaka, "Potential Performance and Feasibility of Immersion Lithography", NGL Workshop 2003, July 10, 2003, Slide Nos. 1-33.  ZR AAR BBR CCR  Examiner  Date Considered: 5/6/20 65  *EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if		1		†		<del>                                     </del>		1	<u>.</u>	$\top$				-			Н
WR  OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)  XR H. Hogan, "New Semiconductor Lithography Makes a Splash", PHOTONICS SPECTRA, Photonics TechnologyWorld, October 2003 Edition, pgs. 1-3  YR S. Owa and N. Nagasaka, "Potential Performance and Feasibility of Immersion Lithography", NGL Workshop 2003, July 10, 2003, Slide Nos. 1-33.  ZR  AAR  BBR  CCR  Examiner Dath of Considered: 5/6/20 65*  "EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if				1				1		$\neg \uparrow \neg$		_	$\top$		_		$\vdash$
XR H. Hogan, "New Semiconductor Lithography Makes a Splash", PHOTONICS SPECTRA, Photonics TechnologyWorld, October 2003 Edition, pgs. 1-3  YR S. Owa and N. Nagasaka, "Potential Performance and Feasibility of Immersion Lithography", NGL Workshop 2003, July 10, 2003, Slide Nos. 1-33.  ZR  AAR  BBR  CCR  Examiner Date Considered: 5/6/20 45  "EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if		1							•		- ·- ·- ·- ·- ·- ·- ·- ·- ·- ·- ·- ·- ·-			- 1			Н
XR H. Hogan, "New Semiconductor Lithography Makes a Splash", PHOTONICS SPECTRA, Photonics TechnologyWorld, October 2003 Edition, pgs. 1-3  YR S. Owa and N. Nagasaka, "Potential Performance and Feasibility of Immersion Lithography", NGL Workshop 2003, July 10, 2003, Slide Nos. 1-33.  ZR  AAR  BBR  CCR  Examiner Date Considered: 5/1/20 45  "EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if	OTHER (In	ıcludi	ng in this order	Author.	Title.	Period	ical Name	e. Date	e. Pertinen	t Page	s. etc.)						
YR S. Owa and N. Nagasaka, "Potential Performance and Feasibility of Immersion Lithography", NGL Workshop 2003, July 10, 2003, Slide Nos. 1-33.  ZR  AAR  BBR  CCR  Examiner  Date Considered: 5/1/20 45  *EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if		T	H. Hogan, "New	Semi	ondu	ctor Lit	hography	Make	s a Splash	", PHC	TONICS				 		
ZR  AAR  BBR  CCR  Examiner Dutted  Date Considered: 5/6/20 45  *EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if	22	YR	S. Owa and N. I	Nagasa	aka, "F	otentia	al Perform	nance	and Feasi	bility of		on .					
BBR CCR Examiner Dutter Date Considered: 5/1/20 45  *EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if		ZR															П
Examiner Duty Date Considered: 5/1/20 65  *EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if		AAR															П
Examiner Duty Date Considered: 5/1/20 65 *EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if		BBR															П
*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if		CCR															
*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if	Examiner	D	May						Date Con	sidered	:5/6	12	06	5			
not in conformance and not considered. Include copy of this form with next communication to Applicant.	_							n is in (	conformanc	e with f	MPEP § 60	9. Dra			ugh	citation i	f

2851

TRV

Docket Number: 081468-0306524 Client Reference: P-0381.020-US PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Re the Application of

LOF et al.

Group Art Unit: 1756

Application No.: 10/705,783

**Examiner: Unassigned** 

Filed: November 12, 2003

Confirmation No.: 5222

For: LITHOGRAPHIC APPARATUS AND DEVICE MANUFACTURING METHOD

January 6, 2005

#### SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents P. O. Box 1450 Alexandria, VA 22313-1450

Sir:

Pursuant to 37 C.F.R. 1.56, the attention of the Patent and Trademark Office is hereby directed to the following U.S. patent application(s):

Examiner's	First Inventor	Application	Filing	Enclosed
Initials		No.	Date	·
2004				
	STREEFKERK et al.	10/844,575	05/13/2004	Specification     ■     Continue
D.K	(081468-0309421)			□ Drawings     □
1				Other: stamped receipt
				card

<sup>\*</sup>The Examiner's initials adjacent a citation indicates he/she has considered the cited application relative to the subject application.

It is respectfully requested that this application and the art cited therein during examination be expressly considered during the prosecution of this application and be made of record in this application. The identification of the above U.S. patent application is not to be construed as a waiver of secrecy as to that application now or upon issuance of the present application as a patent.

<u>PLEASE DO NOT PRINT</u> the above information on the patent which results from this application.

Consideration of each listed application is earnestly solicited since unpublished patent applications are contemplated as IDS material; see the exception in Rule 98(a)(2)(iii) and note the penultimate sentence of MPEP 609.

Further, in keeping with MPEP 609, subsec. C(2), 2nd para., line 10 to end of the paragraph (especially note lines 18-25) **PLEASE <u>RETURN</u> A COPY OF <u>THIS LETTER</u>** with the Examiner's initials adjacent each above listing so that applicant will know that each listed application has been considered as required by PTO policy.

30503621vI

To: U.S.	Departn RM PAT-	(modified) nent of Commerce 1449) rademark Office	JAN	1 P E 1613	Atty. Dkt. No.	M#			Clien	t Ref.		
			E			306524			P-03	81.02	0-US	
INFORM	ATION E	DISCLOSURE STATEME	NT CA	DEMARKS	Applicant:	LOF et al.			1. 00.	71.02	<u> </u>	
BY APPL	LICANT							<u>-</u>				
						10/705,783	40.000					
_		0.0005	Danie	1	) <u> </u>	: November Unknown	12, 200		p Art Un	i+ 45	<u> </u>	851
	January	·	Page 1 of		[Examiner.	OTIKHOWIT		Giou	AICOII		<u> </u>	<u></u>
Examiner		DOCUMENTS Document	Date	Name				Class	Sub		Filing C	- Date
Initials*	13	Number	MMYYYY		ne of First Inver	ntor)		0.000	Class	5	(if approp	
70 7	Z. AR	4,390,273	06/1983	LOEBACH 6				355	125			
1	BR		05/2001	LEE et al.				369	112			
	CR	2002/0020821 A1	02/2002	VAN SANTE	EN et al.			<del>2</del> 50	492			
<b>1</b>	DR	2004/0119954 A1	06/2004	KAWASHIM	IA et al.			355	30			
カタ	ER	2004/0125351	07/2004	KRAUTSCH	IIK et al.			355	53			
FOREIG	N PATEI	NT DOCUMENTS		<del>.</del>					English Ab	stract	Translation Readily Available	
		Document Number	Date MM/YYYY	Country	Inventor Nar	ne				I	-	Tax-
-0.0	+							-	Enclosed	No	Enclosed	INO
DA	7	WO 2004/053596 A2	06/2004	PCT	GRAUPNER				<u>X</u>	+-	<del>├</del> -	+-
	GR	WO 2004/053950 A1	06/2004	PCT	OWA				<u> </u>	┼	<del> </del>	+-
	HR.	WO 2004/053951 A1	06/2004	PCT	MAGOME et				X	$\vdash$	┼	+
	IR	WO 2004/053952 A1	06/2004	PCT	MAGOME et	al.			X	₩	<del> </del>	+
	JR	WO 2004/053953 A1	06/2004	PCT	NEI et al.				X	$\vdash$	<del>                                     </del>	+
	KR	WO 2004/053954 A1	06/2004	PCT	NEI et al.				<u> </u>	₩	<del> </del>	+
	LR	WO 2004/053955 A1	06/2004	PCT	HIRUKAWA		-		X	┼	<del> </del>	╀
	MR	WO 2004/053956 A1	06/2004	PCT <sup>-</sup>	NAGASAKA				X	$\vdash$	<del></del>	+
	NR	WO 2004/053957 A1	06/2004	PCT	HIDAKA et a			$\dashv$	<u> </u>	┼	<del> </del>	+-
	OR	WO 2004/053958 A1	06/2004	PCT	MIZUTANI e	t al.			<u> </u>	$\vdash$	<del> </del>	┼
}	PR	WO 2004/053959 A1	06/2004	PCT	SHIRAI				X	┼	<del> </del>	╀
	QR	WO 2004/055803 A1	07/2004	PCT	VAN SANTE				X	₩	<del></del> -	┼
	RR	WO 2004/057589 A1	07/2004	PCT	NEIJZEN et				X	—	├	╀
	SR	WO 2004/057590 A1	07/2004	PCT	VAN SANTE	N et al.			X	<del> </del> -	<del> </del>	╀
	TR	JP 11-176727	07/1999	JAPAN	SHIRAISHI				X	<del>-</del>	<del>                                     </del>	╄
- TV	UR	JP 2000-058436	02/2000	JAPAN	FUJISHIMA				X	₩	<del> </del>	╀
<i>D.</i> k	C. 1017	JP 2004-193252	07/2004	JAPAN	Not Available				X	┼─	<del> </del>	+
OTHER (		g in this order Author, Tit	le, Periodical N	lame, Date;	Pertinent Pages	s, etc.)				┼	<del> </del>	+-
	WR	<b></b>					./. /	لحي		<u> </u>	]	
Examiner	<b>NXH</b>		<del></del>			idered: 5				<del></del>		<del></del> -
EXAMIN not in cor		Initial if citation consider ce and not considered. In						. Uraw	/ line thr	ough	citation	IT .